

IN THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Canceled)
2. (Canceled)
3. (Canceled)
4. (Canceled)
5. (Canceled)
6. (Canceled)
7. (Canceled)
8. (Original) A method for fabricating a multi-component pattern comprising:
 - (a) defining a first set of regions of localized magnetic field maxima and minima on a substrate;
 - (b) applying magnetic nanoparticles to the substrate so that the magnetic nanoparticles aggregate on the first set of regions of localized magnetic field maxima and avoid regions of localized magnetic field minima;
 - (c) exposing the substrate to a substrate modifying process to modify sites of the substrate without aggregated magnetic nanoparticles;
 - (d) defining a second set of regions of localized magnetic field maxima and minima on the substrate;
 - (e) applying magnetic nanoparticles to the substrate so that the magnetic nanoparticles aggregate on the second set of regions of localized magnetic field maxima and avoid regions of localized magnetic field minima;
 - (f) exposing the substrate to a second substrate modifying process to modify sites of the substrate without aggregated magnetic nanoparticles; and
 - (g) repeating steps (a) through (f) with additional substrate modifying processes.
9. (Canceled)
10. (Canceled)
11. (Canceled)

12. (Canceled)
13. (New) A method for fabricating a multi-component pattern comprising:
 - (a) defining a first set of regions of localized magnetic field maxima and minima on a substrate; and
 - (b) applying magnetic nanoparticles to the substrate so that the magnetic nanoparticles aggregate on the first set of regions of localized magnetic field maxima and avoid regions of localized magnetic field minima.
14. (New) The method of claim 13, further comprising:
 - (c) exposing the substrate to a substrate modifying process to modify sites of the substrate without aggregated magnetic nanoparticles.
15. (New) The method of claim 14, further comprising:
 - (d) defining a second set of regions of localized magnetic field maxima and minima on the substrate;
 - (e) applying magnetic nanoparticles to the substrate so that the magnetic nanoparticles aggregate on the second set of regions of localized magnetic field maxima and avoid regions of localized magnetic field minima; and
 - (f) exposing the substrate to a second substrate modifying process to modify sites of the substrate without aggregated magnetic nanoparticles.
16. (New) The method of claim 15, further comprising:
 - (g) repeating steps (d) through (f) with additional substrate modifying processes.